

8. (Amended) A plate-making apparatus according to claim 7 wherein:  
a pulse width of said ultra-short pulse laser light is not longer than 10 ps.

9. (Amended) A plate-making apparatus according to claim 7, where said photosensitive plate-making material has a photosensitive wavelength not longer than 400 nm, wherein:  
a wavelength of said ultra-short pulse laser light is not longer than 800 nm.

**Please add the following new claims:**

14. (New) A combination comprising:  
a photosensitive plate making material; and  
a plate-forming apparatus for scanning said photosensitive plate-making material by using modulated laser light to record an image on said photosensitive plate-making material, comprising:

a light source for generating laser light including ultra-short pulse laser light which causes photopolymerization reaction by a multiple photon absorption phenomenon at a laser light irradiated portion of said photosensitive plate-making material;

a light modulator for modulating said laser light generated by said light source; and

a light scanning mechanism for scanning said laser light modulated by said light modulator.

15. (New) A combination according to claim 14 wherein:  
a pulse width of said ultra-short pulse laser light is not longer than 10 ps.

16. (New) A combination according to claim 14 wherein:  
a wavelength of said ultra-short pulse laser light is not longer than 800 nm; and  
a photosensitive wavelength of said photosensitive plate-making material is not longer than 400 nm.